PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Emmanuel Hadji et al.

Title:

METHOD FOR FORMING AN OPTICAL SILICON LAYER ON A SUPPORT

AND USE OF SAID METHOD IN THE PRODUCTION OF OPTICAL

COMPONENTS

Docket No.:

33019US1

INFORMATION DISCLOSURE STATEMENT

Mail Stop PATENT APPLICATION Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In accordance with 37 C.F.R. § 1.98, applicant is submitting herewith Form PTO-1449 listing references for consideration by the Examiner. Per 37 C.F.R. § 1.98(d), copies of the references are not required since each reference listed was cited in application Serial No. 09/673,005 filed November 27, 2000.

Respectfully submitted,

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By:

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Date: March 15, 2004

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Page 1 of 1

APPLICANT:

Emmanuel Hadji et al.

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			U.S. PA	TENT DOCU	JMENTS			
Exam. Itl.		Document No.	Date	Name		Class	Subclass	Filing Date
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	М	Yukari Ishikawa et al., Epitaxy-ready Si/SiO ₂ Bragg reflectors by multiple separatio implanted-oxygen, Dec. 16, 1996, pages 3881-3883.						
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*Examiner: Initial if reference considered, regardless of whether citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.